GF100 Series Standard Flow Ultra-High Purity Mass Flow Controller



Flow Ranges from 3 sccm to 55 slm

Process Gas Accuracy: ± 1% of S.P.

MultiFlo[™] gas and range programmability

Best in class performance:

Process gas accuracy

Flow response time

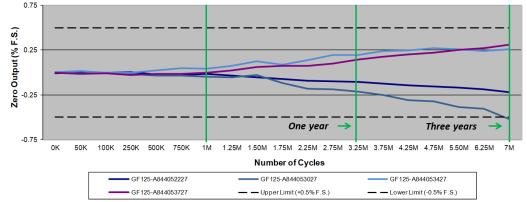
Pressure transient insensitivity

Semiconductor industries leading thermal MFC, over 500,000 in operation

Proven across all processes – Etch, CVD, MOCVD, PVD, Implant, Thermal, Epi, Diffusion, CMP, EUV-Lithography

GF1XX Series		Number of	Comp A, Model A		Number of	Comp B, Model A		Number of
Designator	Range	Platforms	Designator	Range	Platforms	Designator	Range	Platforms
SH40	3 - 10	1	#R01	10	1	FR-01	1 - 5	1
SH41	11 - 30	2	#R01.5	17.5	2	FR-02	6 - 14	2
SH42	31 - 92	3	#01	30	3	FR-03	15 - 27	3
SH43	93 - 280	4	#1.5	55	4	FR-04	28 - 38	4
SH44	94 - 860	5	#02	100	5	FR-05	39 - 71	5
SH45	861 - 2,600	6	#2.5	175	6	FR-06	72 - 103	6
SH46	2,601 - 7,200	7	#03	300	7	FR-07	104 - 192	7
SH47	7,201 - 15,000	8	#3.5	550	8	FR-08	193 - 279	8
SH48	15,001 - 30,000	9	#04	1,000	9	FR-09	280 - 754	9
SH49	30,001 - 40,000	10	#4.5	1,750	10	FR-10	755 - 2,037	10
SH50	40,001 - 55,000	11	#05	3,000	11	FR-11	2,038 - 5,500	11
The Brooks Advantage			#5.5	5,500	12	Comp	B, Model B	
			#6	10,000	13	FR-12	5,501 - 11,000	12
			Comp A, Model B			Comp B, Model C		
			#6.5	22,000	14	FR-13	11,001 - 30,000	13
			#07	30,000	15	Comp	B, Model D	
			#08	50,000	16	FR-14	30,0001 - 50,000	14

More flexibility, less spares and cost of ownership



Excellent long-term zero stability



GF100 Series High-Flow Ultra Compact High Flow MFC



Wide-Range: 56 sccm to 300 slpm (N2 Equiv)

• 700 slm H2 capability

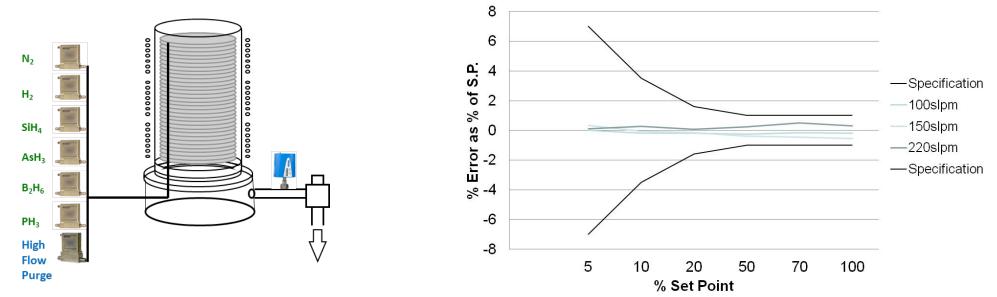
Process Gas Accuracy: ± 1% of S.P.

Hydraulically balance valve for reduced inlet pressure sensitivity

Integrated pressure measurement (GF126)

High flow, low ΔP control

92mm high flow c-seal and 8 VCR configurations





VDM300 Ultra High Purity Water Vapor Delivery Sub-System



Direct water vapor measurement delivering 1% of S.P. accuracy

Operates at low temperatures (non-super heated state) for improved corrosion resistance

Small footprint for easy integration with process tool

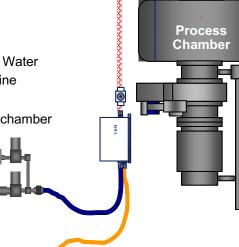
Designed for advanced strip and post metal etch passivation processes

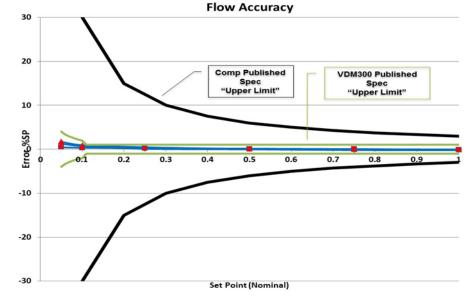
Simple tool integration

- AC power 230 VAC
- ± 15 VDC
- 0-5 VDC Setpoint (Flow)
- A filtered supply of house DI Water
- A regulated Nitrogen purge line
- A drain line (for service)

DI WATER FLOW

A heated delivery line to the chamber







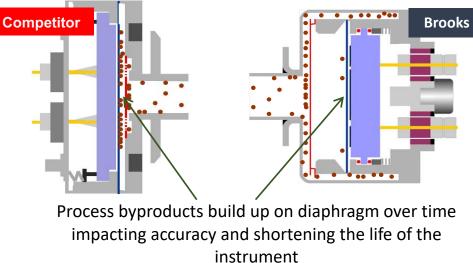
XacTorr[™] - CMX Series High Performance Digital Capacitance Manometer



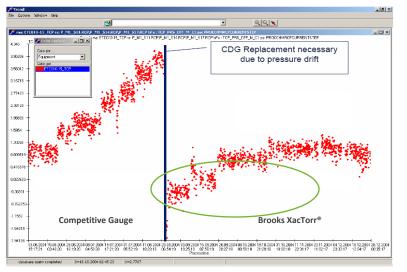
Full scale ranges: 100mT to 1000 Torr

64 point calibration: ± 0.15% of reading accuracy (± 0.25% <1 Torr) Optimum configurations for all processes: Unheated, 45,100 & 160°C Contamination resistant sensor: longer life, lower cost of ownership Industry standard 9-pin,15-pin Analog & DeviceNet interfaces Programmable process relays

Unique independent diagnostic and service port



Longer life, contamination tolerant sensor



Market leading measurement stability

